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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Pascal Huyghe et al.

Date Filed:

June 27, 2003

Title:

Method and System for Electronic Order Entry and

Automatic Processing of Photomask Orders

This application claims the benefit of U.S. Provisional Application Serial No. 60/392,567 filed June 28, 2002

Honorable Assistant Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 I hereby certify that this Information Disclosure Statement is being deposited with the United States Postal Service as Express Mail No. EV341121137US addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on the date shown below.

Shannon Judice

Dear Sir:

INFORMATION DISCLOSURE STATEMENT

Applicants respectfully request, pursuant to 37 C.F.R. §§1.56, 1.97 and 1.98, that the references listed on the attached PTO-1449 form be considered and cited in the examination of the above-identified application. Copies of the references are enclosed for the convenience of the Examiner. Furthermore, pursuant to 37 C.F.R. §§1.97 (g) and (h), no representation is made that these references are material to the patentability of the present application.

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Applicants believe no fee is due, however, the Commissioner is hereby authorized to charge any additional fees or credit any overpayments to Deposit Account No. 50-2148 of Baker Botts L.L.P.

Respectfully submitted,

BAKER BOTTS L.L.P. Attorneys for Applicants

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Date: June 27, 2003

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Page 1 of 1

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